

# *TurboDisc* K465i GaN MOCVD System

Highest Capital Efficiency GaN MOCVD System  
Combines Industry's Highest Productivity  
With Best-in-Class Yields



- Superior uniformity and repeatability with new Uniform FlowFlange® technology
- Industry's highest productivity due to full automation and one-run recovery period after maintenance
- Low maintenance TurboDisc® technology enables highest system availability
- Production-proven platform



Solutions for a nanoscale world.™

# TurboDisc K465i GaN MOCVD System

The TurboDisc K465i™ GaN MOCVD System is the newest entry into Veeco's K-Series platform, which is production-proven and provides high productivity and high capital efficiency in HB LED high-volume production fabs around the globe. The K465i achieves up to 90% yield (5nm bin) due to its superior uniformity and excellent run-to-run repeatability. It also offers the industry's highest productivity due to its full automation and shortened recovery period after maintenance.

At the heart of the TurboDisc K465i GaN MOCVD System is Veeco's patent-pending Uniform FlowFlange® technology, which was designed to create a uniform alkyl and hydride flow pattern across all wafers. This results in superior uniformity and repeatability with the industry's lowest particle generation. The FlowFlange's simplified design provides ease-of-tuning for fast process optimization on wafer sizes up to 8 inches and fast tool recovery time after maintenance for the LED industry's highest productivity.

## K465i Productivity Advantage

### MINIMAL MAINTENANCE AND HIGHEST THROUGHPUT

- Low maintenance TurboDisc technology enables highest system availability and throughput
- Uniform laminar flow provides for clean reactor during all growths
- No daily in-situ bakes needed and no daily or weekly cleaning required



Fully automated, production-proven platform

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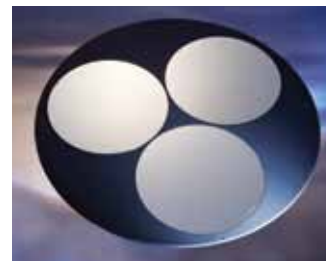
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## Cost-Saving Extendibility

SEAMLESS TRANSITION TO LARGER WAFER SIZES UP TO 8"



12 x 4"

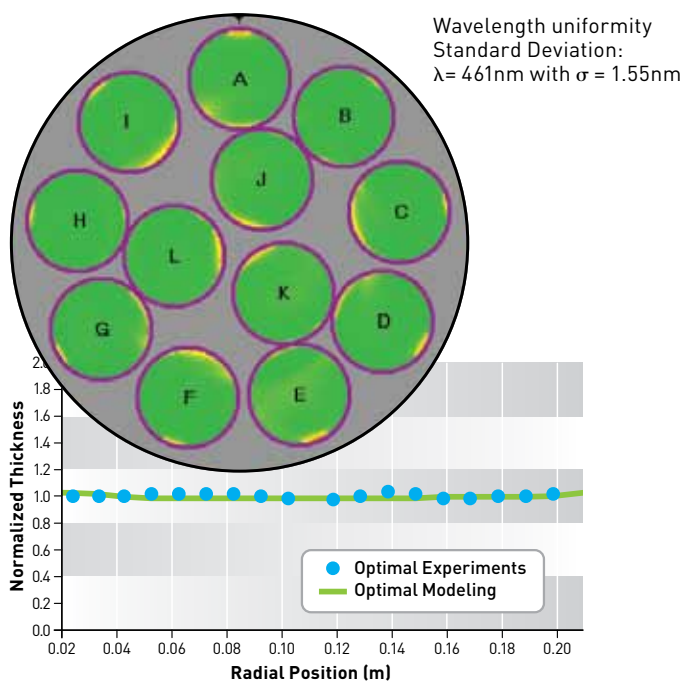


3 x 8"

## Superior Wavelength Uniformity

### CAPABLE OF ACHIEVING 90% YIELD IN 5nm BIN

- Superior within-wafer uniformity
- Excellent wafer-to-wafer repeatability



Excellent thickness uniformity across wafer carrier



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Find out more at [www.veeco.com/mocvd](http://www.veeco.com/mocvd) or call 1.888.24.VEECO